BILATAL ANODISING

The specific characteristic of this coating is the high resistance to and low reflection of UV radiation. Consequently, the coating is particularly applied in the lithographic industry. Aluminium has to undergo surface treatment before it can be applied in lithographic systems. This is because uncontrolled oxidation of aluminium may result in particle contamination in the system. The bilatal method has been developed to avoid this contamination.

Characteristics
- Low reflection and high resistance under UV conditions
- Layer thickness 12 ± 2 µm
- Electric insulating layer
- Almost no influence on dimensions; this is compensated by dimensional pickling

Applications
Lithographic systems parts

Approvals
ASML